

REMARKS

In response to the Restriction Requirement of June 2, 2003, Applicants thereby elect Claims 1-33, drawn to a method for forming a resist image comprising using carbon dioxide in both the deposition and developing steps. This election is being made with traverse, because Applicants respectfully submit that, as amended, Claims 34-67 also are drawn to a method for forming a resist image comprising using carbon dioxide in both the deposition and developing steps.

In particular, independent Claims 34 and 67 both have been amended to recite "contacting the at least one wafer with a first composition comprising carbon dioxide and a component selected from the group consisting of...." Thus, remaining independent Claims 34 and 67 also are drawn to a method for forming a resist image comprising using carbon dioxide in both the deposition and developing steps. These amendments have been made to expedite examination of all the pending claims, without prejudice to the filing of a continuing application for original Claims 34-67. Accordingly, distinct subcombinations are no longer claimed, and the rationale for requiring restriction has now become moot.

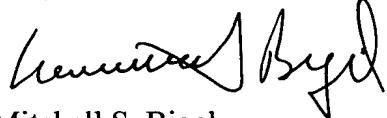
Claim 1 has been amended to provide proper antecedent basis for the "first composition" and to correct a typographical error. Claims 9, 25 and 39 have been amended to correct a typographical error. Claims 34 and 67 also have been amended to provide proper antecedent basis for the Integrated Microelectronics Process Device (IMPD). Finally, Claim 64 has been amended to supply the missing chemical formula.

In view of the above, Applicants provisionally elect Claims 1-33. However, Applicants respectfully submit that all of the pending claims now are directed to a method for forming a resist image comprising using carbon dioxide in both the

In re: DeSimone et al.
Serial No.: 09/975,211
Filed: October 10, 2001
Page 16 of 16

deposition and developing steps. Accordingly, Applicants respectfully request examination and allowance of all of pending Claims 1-67.

Respectfully submitted,



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CERTIFICATE OF MAILING

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Susan E. Freedman
Date of Signature: July 1, 2003